

Docket Number: 081468-0306781
Client Reference: P-0381.010-US



IRW
PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of

LOF et al.

Group Art Unit: 1756

Application No.: 10/705,805

Examiner:

Filed: November 12, 2003

Confirmation No.: 5288

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
	DIERICHS (081468-0308270)	10/775,326	02/11/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	DUINEVELD et al. (081468-0308101)	10/773,461	02/09/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	FLAGELLO et al. (081468-0302644)	10/698,012	10/31/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	SUWA et al. (Reissue Application of U.S. Patent No. 6,191,429 B1)	10/367,910	02/19/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input type="checkbox"/> Other: stamped receipt card

*The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

It is respectfully requested that these applications and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent applications is not to be construed as a waiver of secrecy as to those applications now or upon issuance of the present application as a patent.

PLEASE DO NOT PRINT the above information on the patent which results from this application.

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Consideration of each listed application is earnestly solicited since unpublished patent applications are contemplated as IDS material; see the exception in Rule 98(a)(2)(iii) and note the penultimate sentence of MPEP 609.

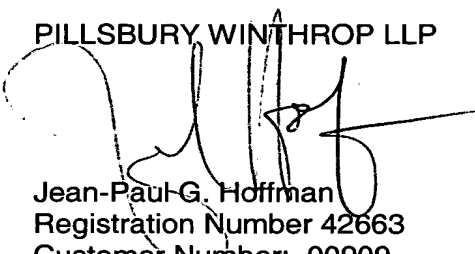
Further, in keeping with MPEP 609, subsec. C(2), 2nd para., line 10 to end of the paragraph (especially note lines 18-25) **PLEASE RETURN A COPY OF THIS LETTER** with the Examiner's initials adjacent each above listing so that applicant will know that each listed application has been considered as required by PTO policy.

Secondly, please consider each document which is listed on the attached Form PTO-1449 and return a copy of that form with the Examiner's initials adjacent each citation, a copy of each document enclosed except for any U.S. patents and published patent applications. It is respectfully requested that these documents listed on the Form PTO-1449 be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

Respectfully Submitted,

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Atty.
Dkt. No.

M#

Client Ref.

306781

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: LOF et al.

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Filing Date: November 12, 2003

Date: June 2, 2004

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Examiner:

Group Art Unit: 1756

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR	2004/0075895 A1	04/2004	LIN			
	BR						
	CR						
	DR						
	ER						
	FR						
	GR						
	HR						

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name		English Abstract		Translation Readily Available	
							Enclosed	No	Enclose	No
	IR	JP 07-132262	05/1995	JAPAN	HIRAKAWA <i>et al.</i>	X				
	JR	JP 58-202448	11/1983	JAPAN	KAWAMURA <i>et al.</i>	X				
	KR	WO2004/019128	03/2004	PCT	OMURA <i>et al.</i>					
	LR	WO 03/077037	09/2003	PCT	ROSTALSKI					
	MR	WO 03/077036	09/2003	PCT	SCHUSTER	X				
	NR	DD 206 607	02/1984	GERMANY	WESTPHAL <i>et al.</i>			X		
	OR	DD 221 563	04/1985	GERMANY	PFORR <i>et al.</i>			X		
	PR									
	QR									

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

	RR	S. OWA <i>et al.</i> , "Update on 193nm immersion exposure tool", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-51			
	SR	H. HATA, "The Development of Immersion Exposure Tools", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-22			
	TR	T. MATSUYAMA <i>et al.</i> , "Nikon Projection Lens Update", SPIE Microlithography 2004, 5377-65, March, 2004			
	UR	"Depth-of-Focus Enhancement Using High Refractive Index Layer on the Imaging Layer", IBM Technical Disclosure Bulletin, Vol. 27, No. 11, April 1985, p. 6521			
	VR	A. SUZUKI, "Lithography Advances on Multiple Fronts", EEdesign, EE Times, January 5, 2004			
	WR	B. LIN, "The k_3 coefficient in nonparaxial λ/NA scaling equations for resolution, depth of focus, and immersion lithography, <i>J. Microlith., Microfab., Microsyst.</i> 1(1):7-12 (2002)			
	XR				
	YR				
	ZR				

Examiner

Date Considered:

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.